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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet	1	of	4	Attorney Docket Number	14434.4001
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U.S. PATENT DOCUMENTS

Examiner Initials	Cite No. ¹	U.S. Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number-Kind Code ² (if known)		
<i>W.B.</i>	AA	US 2004/0070772 A1	04-15-2004	Shchegrov et al.
<i>W.B.</i>	AB	US 2004/0017574 A1	01-29-2004	Vuong et al.
<i>W.B.</i>	AC	US 2003/0206298 A1	11-06-2003	Bischoff et al.
<i>W.B.</i>	AD	US 2002/0101585 A1	08-01-2002	Benesch et al.
<i>W.B.</i>	AE	US 2002/0051564 A1	05-02-2002	Benesch et al.
<i>W.B.</i>	AF	US 6,721,052 B2	04-13-2004	Zhao et al.
<i>W.B.</i>	AG	US 6,704,661 B1	03-09-2004	Opsal et al.
<i>W.B.</i>	AH	US 6,694,284 B1	02-17-2004	Nikoonahad et al.
<i>W.B.</i>	AI	US 6,694,275 B1	02-17-2004	Jakadar et al.
<i>W.B.</i>	AJ	US 6,689,519 B2	02-10-2004	Brown et al.

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	T ⁶
		Country ³ Number ⁴ Kind Code ⁵ (if known)			
	BA				
	BB				

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

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<i>W.B.</i>	CA	LOGOFATU, PETRE C., "UV Scatterometry," Proceedings of SPIE: Metrology, Inspection, and Process Control for Microlithography XVII, May 2003, pp. 208-214, Vol. 5038, The International Society for Optical Engineering (SPIE), Bellingham, Washington, USA.	
<i>W.B.</i>	CB	HETTWER, ANDREA et al., "Phi-Scatterometry for Integrated Linewidth and Process Control in DRAM Manufacturing," IEEE Transactions on Semiconductor Manufacturing, November 2002, pp. 470-477, Vol. 15, No. 4, Institute of Electrical and Electronics Engineers (IEEE), New York, New York, USA.	

Examiner Signature		Date Considered	1 Nov 2004
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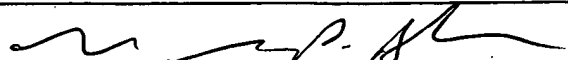
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>				Complete if Known	
				Application Number	10/718,780
				Filing Date	November 20, 2003
				First Named Inventor	Mehrdad NIKOONAHAD
				Art Unit	Not Yet Assigned
Examiner Name	Not Yet Assigned				
Sheet	2	of	4	Attorney Docket Number	14434.4001

U.S. PATENT DOCUMENTS				
Examiner Initials	Cite No. ¹	U.S. Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number-Kind Code ² (if known)		
N.A.	DA	US 6,665,071 B2	12-16-2003	Hovinen et al.
N.A.	DB	US 6,645,824 B1	11-11-2003	Yang et al.
N.G.	DC	US 6,636,843 B2	10-21-2003	Doddi et al.
N.D.	DD	US 6,633,831 B2	10-14-2003	Nikoonahad et al.
N.D.	DE	US 6,608,690 B2	08-19-2003	Niu et al.
N.B.	DF	US 6,608,686 B1	08-19-2003	Lane et al.
N.A.	DG	US 6,583,731 B2	06-24-2003	Chan et al.
J.B.	DH	US 6,483,580 B1	11-19-2002	Xu et al.
N.R.	DI	US 6,451,621 B1	09-17-2002	Rangarajan et al.
N.A.	DJ	US 6,433,878 B1	08-13-2002	Niu et al.

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	EA			
	EB			

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N.A.	FA	NIU, XINHUI et al., "Specular Spectroscopic Scatterometry," IEEE Transactions on Semiconductor Manufacturing, May 2001, pp. 97-111, Vol. 14, No. 2, Institute of Electrical and Electronics Engineers (IEEE), New York, New York, USA.	
N.B.	FB	SCHNEIDER, CLAUS et al., "Integrated metrology: An enabler for advanced process control (APC)," Proceedings of SPIE: In-Line Characterization, Yield, Reliability, and Failure Analysis in Microelectronic Manufacturing II, April 2001, pp. 118-130, Vol. 4406, The International Society for Optical Engineering (SPIE), Bellingham, Washington, USA.	

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<i>W.B.</i>	GA	US 6,429,943 B1	08-06-2002	Opsal et al.
<i>W.B.</i>	GB	US 6,323,946 B1	11-27-2002	Norton
<i>W.B.</i>	GC	6,124,924	09-26-2000	Feldman et al.
<i>W.B.</i>	GD	5,771,094	06-23-1998	Carter et al.
<i>W.B.</i>	GE	5,747,813	05-05-1998	Norton et al.
<i>W.B.</i>	GF	5,608,526	03-04-1997	Piwonka-Corle et al.
<i>W.B.</i>	GG	5,604,344	02-18-1997	Finarov et al.
<i>W.B.</i>	GH	5,596,411	01-21-1997	Fanton et al.
<i>W.B.</i>	GI	5,412,473	05-02-1995	Rosencwaig et al.
<i>W.B.</i>	GJ	5,329,357	07-12-1994	Bernoux et al.

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	HA			
	HB			

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<i>W.B.</i>	IA	BENESCH, NORBERT et al., "Phi-Scatterometry for Integrated Linewidth Control in DRAM Manufacturing," 2001 IEEE International Symposium on Semiconductor Manufacturing, October 8-10, 2001, pp. 129-132, IEEE Catalog No. 01CH37203, San Jose, California, USA.	
<i>W.B.</i>	IB	COULOMBE, STEPHEN A. et al., "Scatterometry measurement of sub-0.1 μ m linewidth gratings," Journal of Vacuum Science & Technology B: Microelectronics and Nanometer Structures, January, 1998, pp. 80-87, Vol. 16, Issue 1, American Vacuum Society, Research Triangle Park, North Carolina, USA.	

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<i>W.B.</i>	JA	5,181,080	01-19-1993	Fanton et al.
<i>W.B.</i>	JB	5,042,951	08-27-1991	Gold et al.
<i>W.B.</i>	JC	4,999,014	03-12-1991	Gold et al.

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	KA				
	KB				

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<i>W.B.</i>	LA	RAYMOND, CHRISTOPHER J. et al., "Multiparameter grating metrology using optical scatterometry," Journal of Vacuum Science & Technology B: Microelectronics and Nanometer Structures, March, 1997, pp. 361-368, Vol. 15, Issue 2, American Vacuum Society, Research Triangle Park, North Carolina, USA.	
<i>W.B.</i>	LB	GIOVANNINI, H. et al., "Angle-resolved polarimetric phase measurement for the characterization of gratings," Optics Letters, October 15, 1996, pp. 1619-1621, Vol. 21, No. 20, Optical Society of America, Washington, DC, USA.	

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